## United States Patent [19]

## Quinn et al.

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[54]	ANAESTH MASK	ETIC AND RESPIRATORY FACE
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[**]	Term:	14 Years
[21]	Appl. No.:	134,910
[22] [52] [58]	[52] U.S. Cl D29/7	
[56]		References Cited
U.S. PATENT DOCUMENTS		
	3,303,845 2/3 3,948,255 4/3	1982 Bushman D29/7   1967 Detmer III D29/7   1976 Davidson 128/202.28   1985 McGinnis 128/202.28
Primary Examiner—Wallace R. Burke		

Assistant Examiner—Kay H. Chin Attorney, Agent, or Firm—R. Stephen Hansell

[57] CLAIM

The ornamental design for an anaesthesia and respiratory face mask, as shown and described.

## **DESCRIPTION**

FIG. 1 is a front perspective view of an anaesthesia and respiratory face mask showing our new design;

FIG. 2 is as rear perspective view thereof;

FIG. 3 is a top plan view thereof;

FIG. 4 is a bottom plan view thereof;

FIG. 5 is a cross sectional view taken along the line 5—5 of FIG. 3.

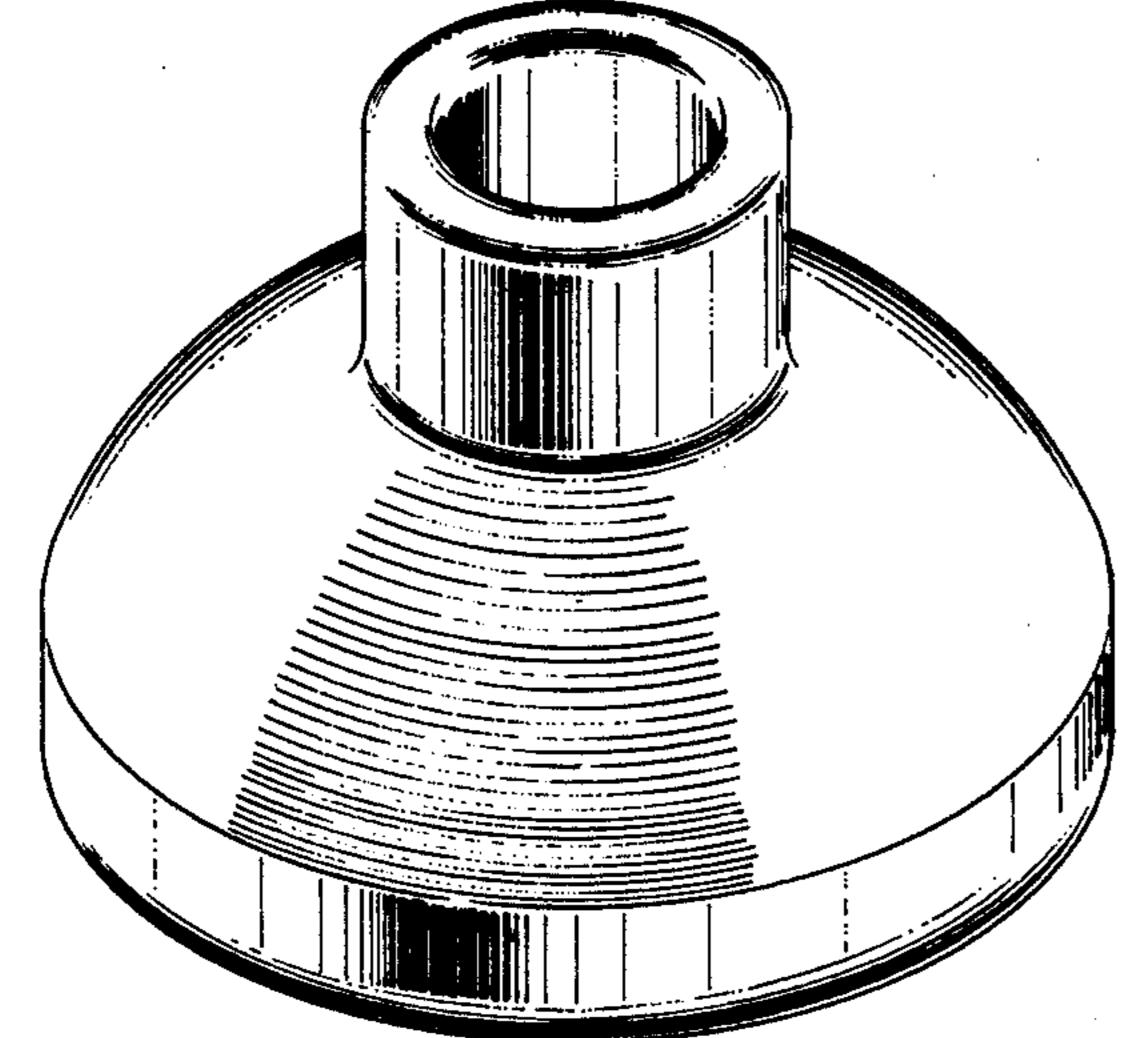
FIG. 6 is a front perspective view of a second embodiment of the anaesthesia and respiratory face mask the sole difference from the first embodiment being in the size of the cylindrical aperture at the front of the mask;

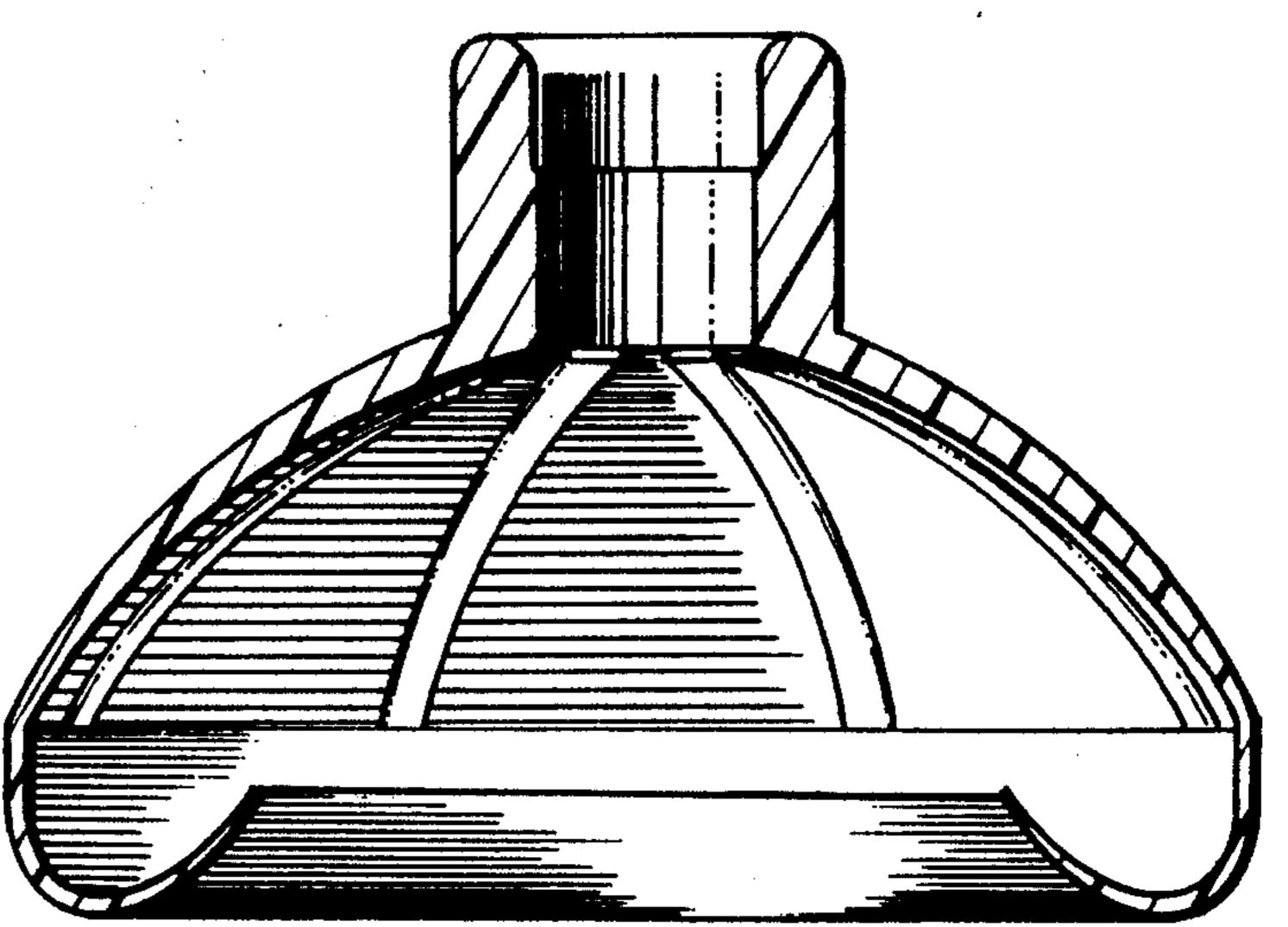
FIG. 7 is a rear perspective view of FIG. 6;

FIG. 8 is a top plan view thereof;

FIG. 9 is a bottom plan view thereof;

FIG. 10 is a cross sectional view taken along the line 5—5 of FIG. 8.





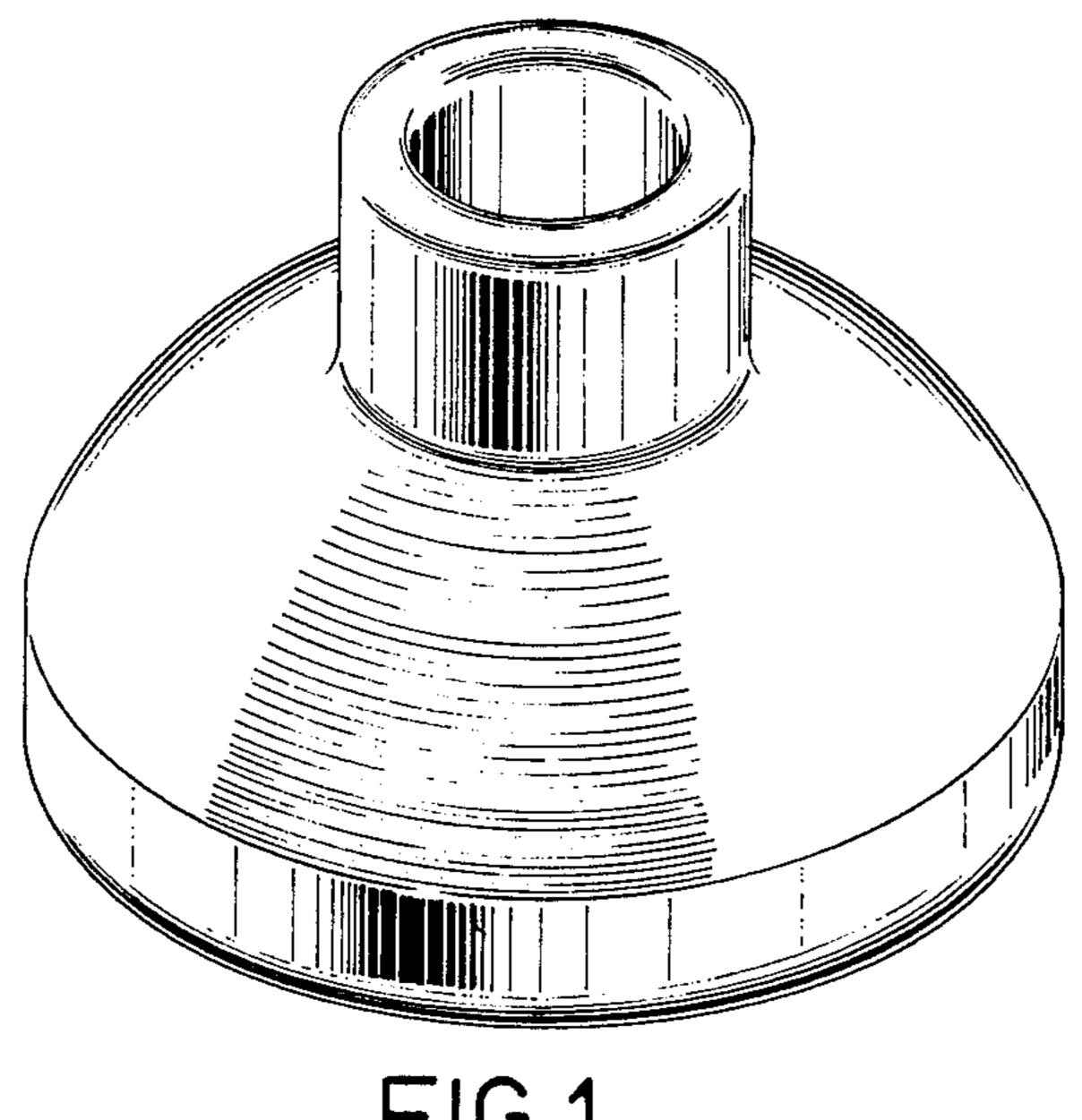


FIG.1

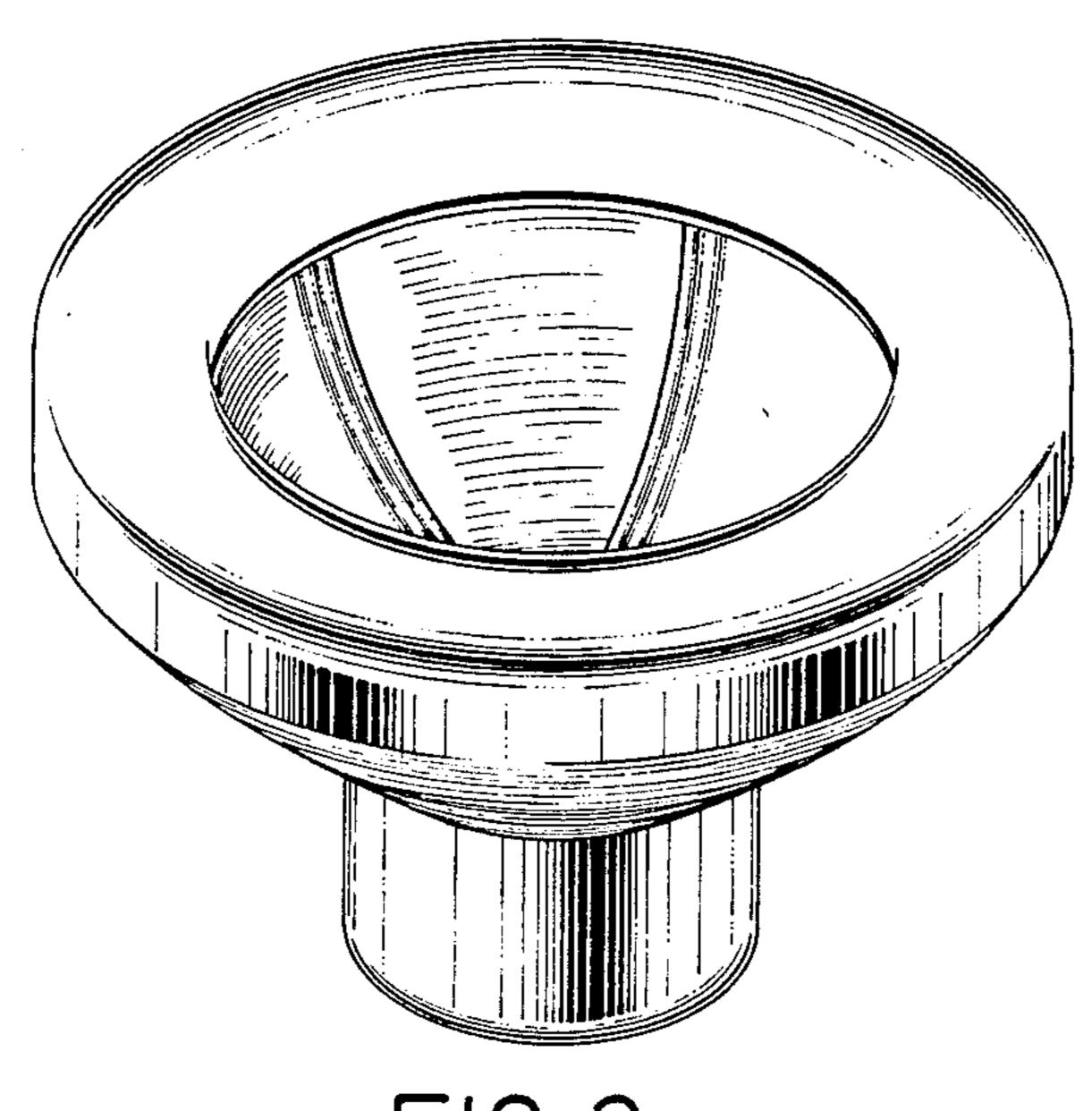
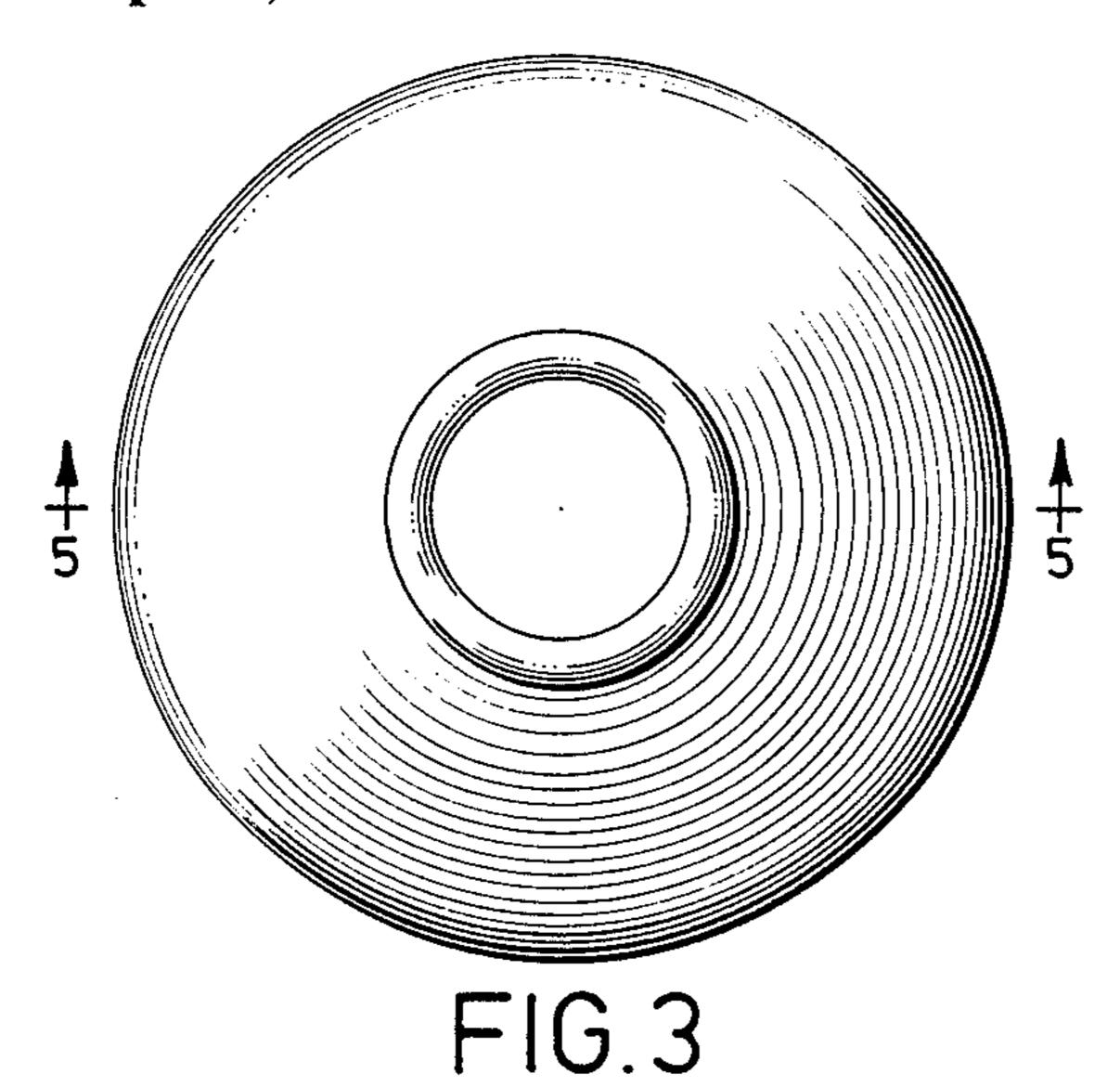
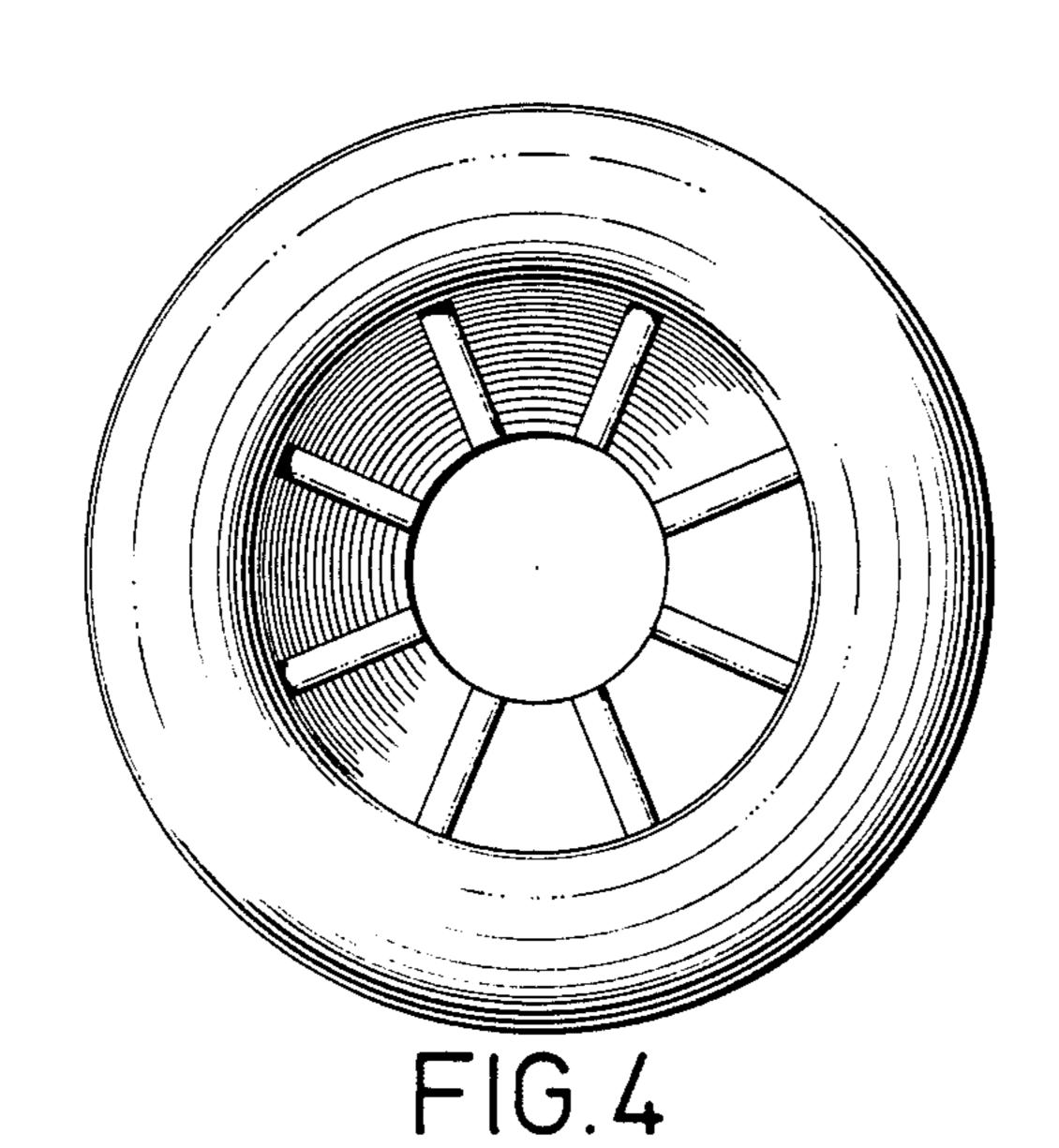
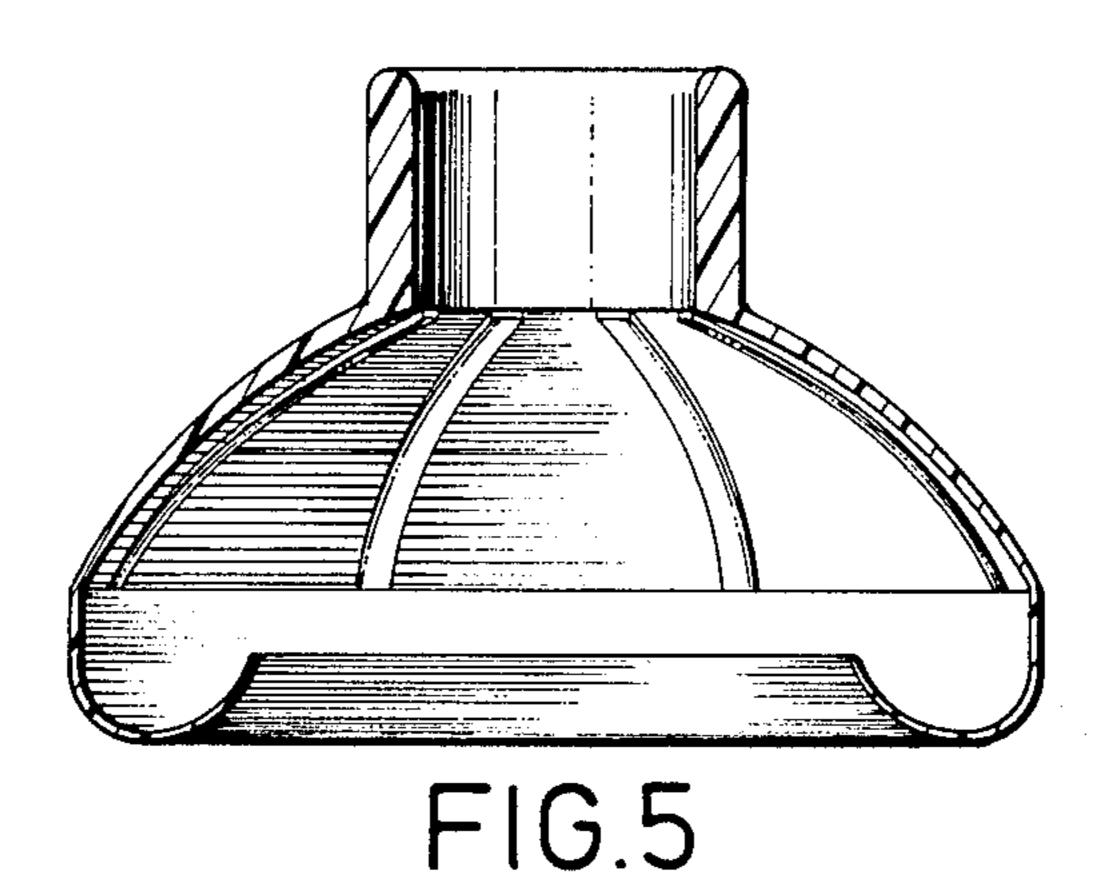


FIG. 2

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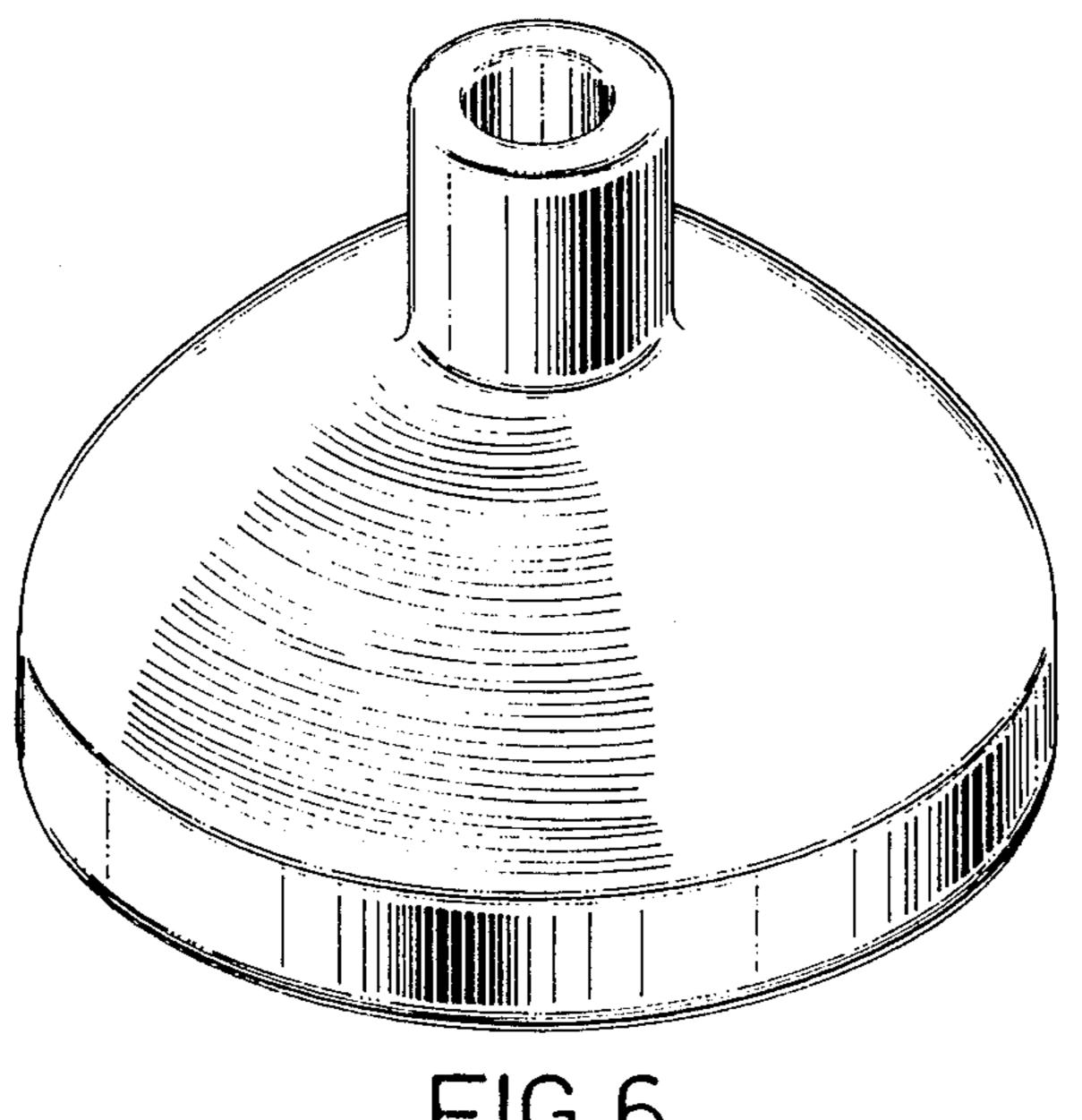
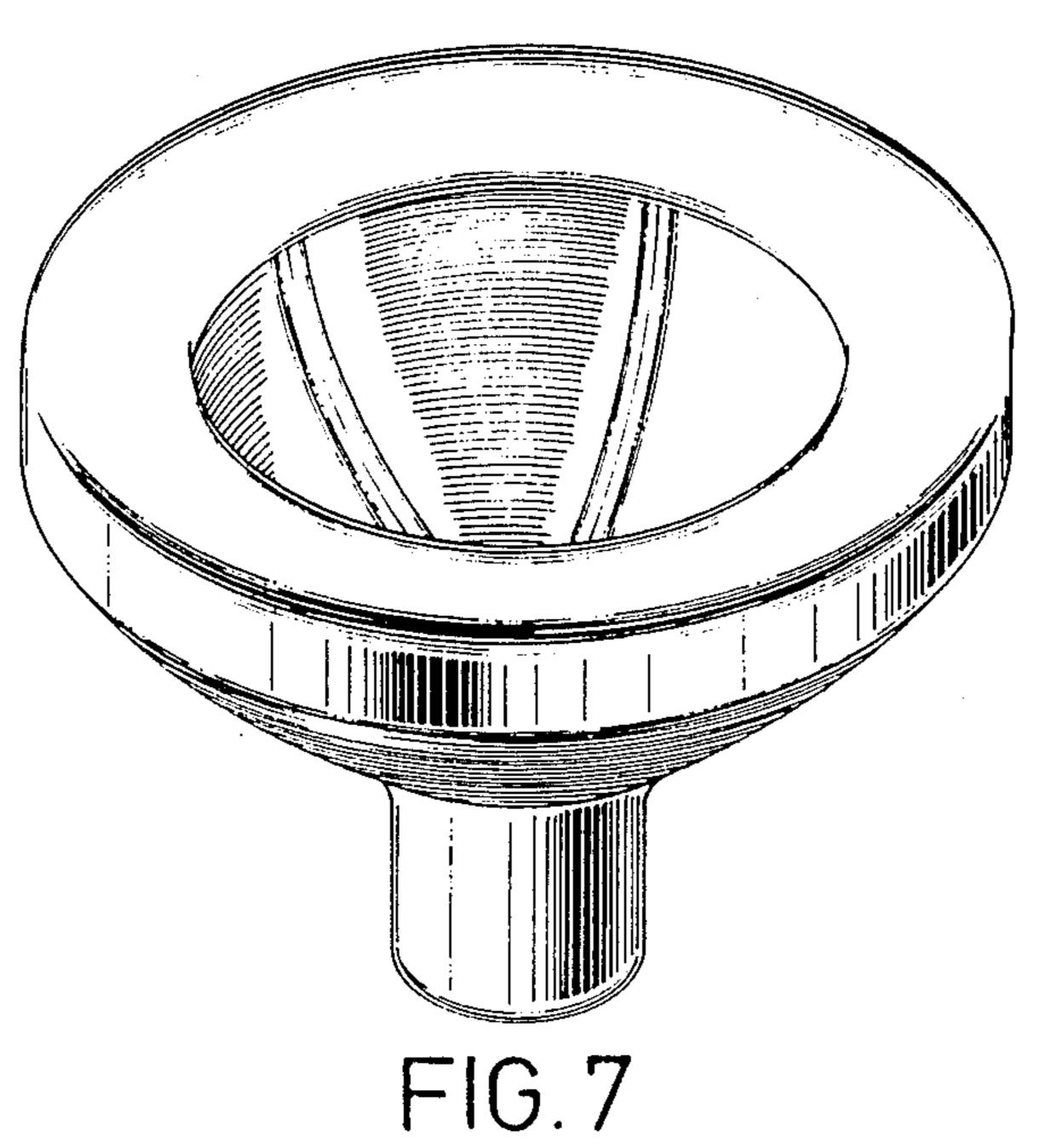


FIG.6



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